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# Semiconductor Devices (EE336)

## Lec. 4: Carrier concentration and Fermi level

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Wed. Oct. 19<sup>th</sup>, 2016

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# Lecture Outline

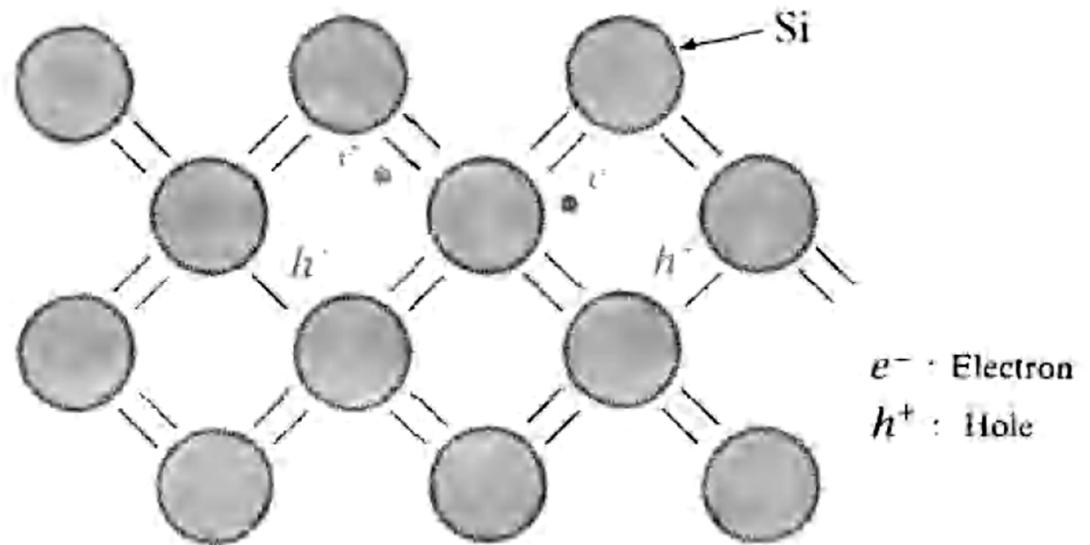
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- ❑ Intrinsic versus extrinsic SCs
- ❑ Donor and acceptor ionization energy
- ❑ Derivation of carrier concentrations based on Fermi-Dirac statistics and density of states
- ❑ Fermi level and its change relative to its intrinsic level with doping

# Intrinsic semiconductors

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- Perfect Semiconductor (no impurities, No lattice defects).
- Thermal excitation breaks one covalent bond producing an electron and a hole free to move across the lattice



Chemical bond model of intrinsic Si

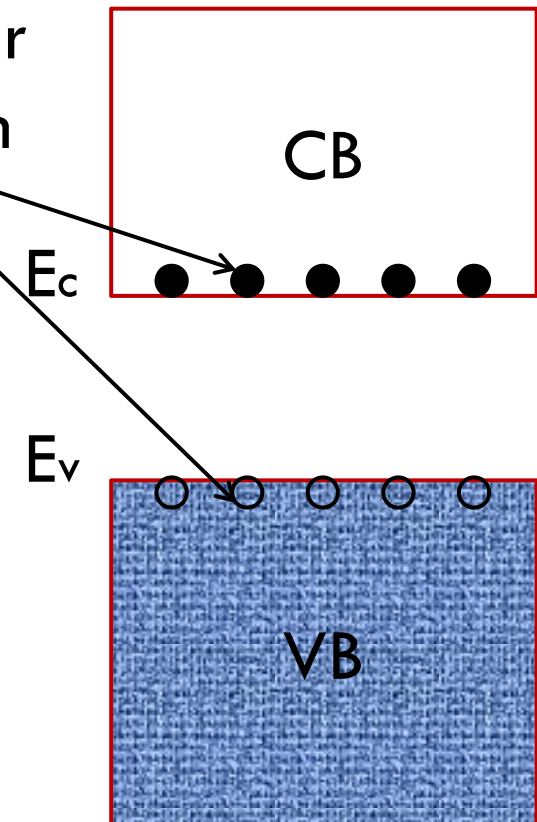
# Intrinsic semiconductors

4

- Perfect Semiconductor  
(no impurities, No lattice defects).

- rate of generation,  $g_i$   
due to thermal excitation  
at  $T > 0$

Electron-Hole Pair  
(EHP) generation



$n$  electrons/ unit volume in CB  
 $p$  holes/unit volume in VB

$$n = p = n_i$$

At temperature  
( $T > 0$  K)

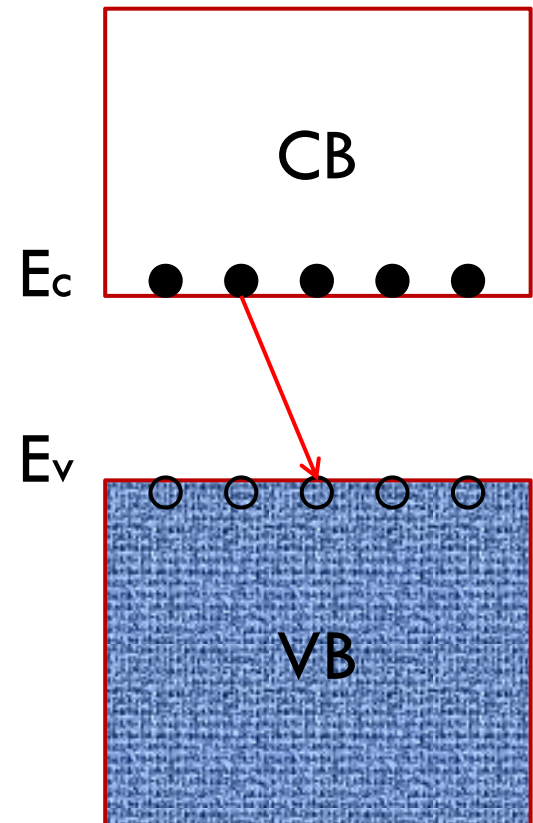
# Intrinsic semiconductors

5

- Perfect Semiconductor  
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- rate of generation,  $g_i$   
due to thermal excitation  
at  $T > 0$

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 $n = p = n_i$



At temperature  
( $T > 0$  K)

# Intrinsic semiconductors

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- Perfect Semiconductor (no impurities, No lattice defects).

- rate of generation,  $g_i$  due to thermal excitation at  $T > 0$

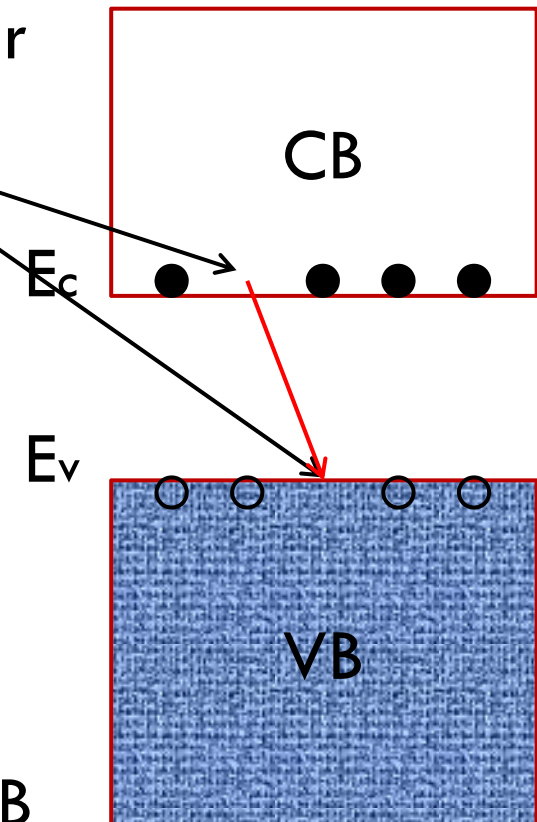
- rate of recombination,  $r_i$  must equal  $g_i$  to have a constant steady state carrier concentration **(thermal equilibrium)**

$n$  electrons/ unit volume in CB

$p$  holes/unit volume in VB

$$n = p = n_i$$

Electron-Hole Pair (EHP) recombination



At temperature  $(T > 0 \text{ K})$

# Intrinsic semiconductors

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$$r_i = g_i$$

$$n_o = p_o = n_i$$

$$r_i \propto n_o p_o$$

$$r_i = \alpha_r n_o p_o = g_i = \alpha_r n_i^2$$

$\alpha_r$  : constant

- Of course  $n_i$  is temperature dependent and will later be derived
- Also  $g_i$  and  $r_i$  are temperature dependent
- At room temperature, Si has  $n_i$  of about  $10^{10}$  EHP/cm<sup>3</sup> which is too small compared to its atomic density of  $5 \times 10^{22}$  atoms/cm<sup>3</sup>
- Via doping, we can change this carrier density and hence manipulate the conductivity of Si

# Extrinsic semiconductors

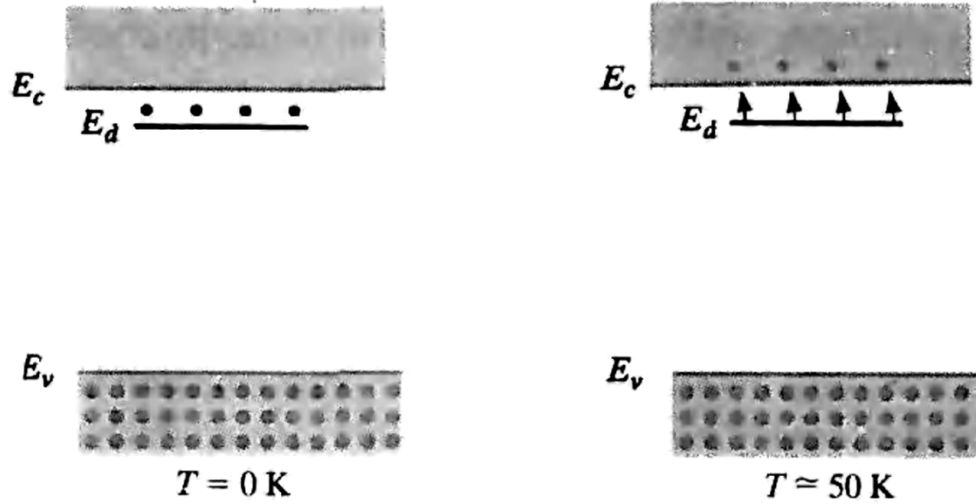
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- Impurities introduced via doping process to vary conductivity of SC
- Doping increases the concentration of one type of carrier (either electrons or holes) compared to the intrinsic concentration  $n_i$  due to thermal excitation and hence increases the conductivity of SC
- N-type doping by adding pentavalent (valency = 5) atoms such as As and P
- P-type doping by adding trivalent (valency = 3) atoms such as B, Al, Ga
- Introducing impurities creates additional energy levels typically lying within the bandgap of SC either very near its CB (n-type doping) or its VB (p-type doping)



# Extrinsic semiconductors (n-type)

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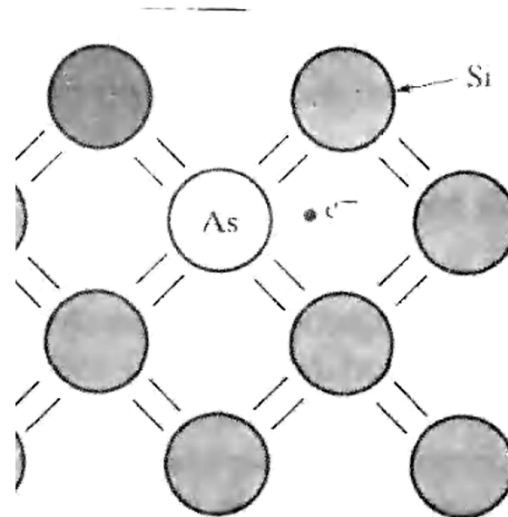


$$n_0 \gg n_i$$

$$n_0 \gg p_0$$

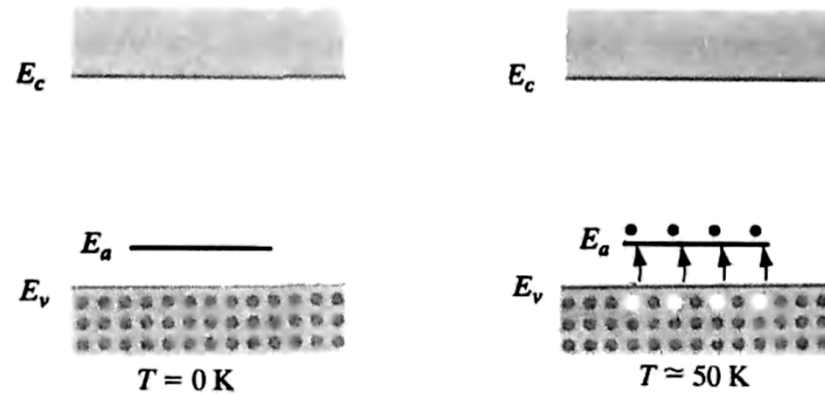
$$n_0 \approx N_D$$

Donor concentration ( $\text{cm}^{-3}$ )



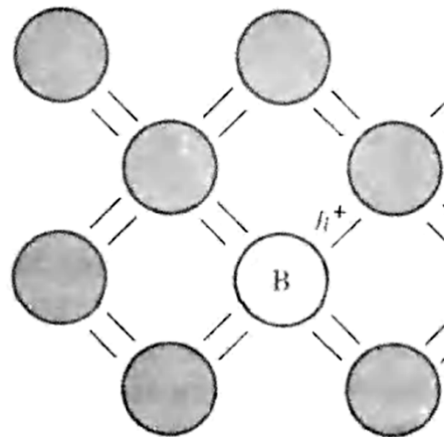
# Extrinsic semiconductors (p-type)

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$$\begin{aligned} p_0 &\gg n_i \\ p_0 &\gg n_0 \\ p_0 &\approx N_A \end{aligned}$$

↓  
Acceptor concentration ( $\text{cm}^{-3}$ )



# Donor and acceptor ionization energy calculation

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- What we mean by ionization energy  $E_{ion}$  is the energy (thermal) required to excite an electron from  $E_d$  to  $E_c$ , i.e.  $E_c - E_d$ , or from  $E_v$  to  $E_a$ , i.e.  $E_a - E_v$
- This is typically a very small quantity relative to the bandgap of SC
- The calculation is made by treating the donor atom, which has 5 valence electrons, as a Hydrogen atom and use the Bohr model
- The four tightly bound electrons that contributed to four covalent bonds will be shielded with the nucleus and all core electrons leaving only a single electron in a Hydrogen-like orbit
- We can then use Bohr's model relationship to calculate the energy to move this electron from  $n = 1$  to  $n = \infty$  and become a free electron thus ionizing the donor atom as

$$E_{ion} = \frac{mq^4}{2(4\pi\epsilon_0\epsilon_r)^2\hbar^2} = \frac{mq^4}{8(\epsilon_0\epsilon_r)^2h^2}$$

# Donor and acceptor ionization energy calculation

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Ex: Calculate  $E_{ion}$  for n-doped Si crystal

$$E_{ion} = \frac{mq^4}{8(\epsilon_0\epsilon_r)^2 h^2}$$

$$m_n^* = \frac{1}{3}m_0, \epsilon_r = 11.9$$

$$\begin{aligned} E_{ion} &= \frac{9.11 * 10^{-31} * (1.6 * 10^{-19})^4}{3 * 8 * 11.9^2 * (8.85 * 10^{-12})^2 * (6.63 * 10^{-34})^2} \\ &= 0.000005102 * 10^{-15} \text{ J} \\ &= \frac{0.000005102 * 10^{-15}}{1.6 * 10^{-19}} \text{ eV} \\ &= 0.032 \text{ eV} \end{aligned}$$

# Donor and acceptor ionization energy actual measured values

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## Ionization energy of selected donors and acceptors in silicon

	Donors			Acceptors		
Dopant	Sb	P	As	B	Al	In
Ionization energy, $E_c - E_d$ or $E_a - E_v$ (meV)	39	44	54	45	57	160

- Because the ionization energy is too small, all electrons due to donors will be present in CB even at very low temperatures whereas EHP generation due to excitation of electrons from VB to CB will typically start at higher temperature because  $E_g$  is larger than  $E_{ion}$
- Remember that each donor atom contributes one electron and vice versa each acceptor atom contributes one hole

# Carrier concentration (Electrons and holes)

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$$n_0 = \int_{E_c}^{\text{top of conduction band}} f(E) N_c(E) dE$$

Electron concentration in  
CB per unit volume ( $\text{cm}^{-3}$ )  
at thermal equilibrium

Probability of occupancy  
of states as a function of  
their energy

Density of states  
(number of states per unit  
volume that may or may not  
be filled with electrons in CB)

- The integration will be made from  $E_c$  to infinity because as we will see  $f(E)$  will become negligibly small as energy increases beyond top of CB
- Both density of states and probability of occupancy should be derived separately before making integration above
- We will use final expressions of  $f(E)$  and  $N(E)$  → for complete derivation of both see appendices IV and V in textbook

# Carrier concentration (Electrons and holes)

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$$n_0 = \int_{E_c}^{\text{top of conduction band}} f(E) N_c(E) dE$$

Electron concentration in  
CB per unit volume ( $\text{cm}^{-3}$ )  
at thermal equilibrium

Probability of occupancy  
of states as a function of  
their energy

Density of states  
(number of states per unit  
volume per unit energy that  
may or may not be filled with  
electrons in CB)  $\rightarrow \text{eV}^{-1}.\text{cm}^{-3}$

$$p_0 = \int_{\text{bottom of valence band}}^{E_v} [1 - f(E)] N_v(E) dE$$

Probability that states are empty, i.e.  
probability that holes exist at these states

# Fermi-Dirac distribution $f(E)$

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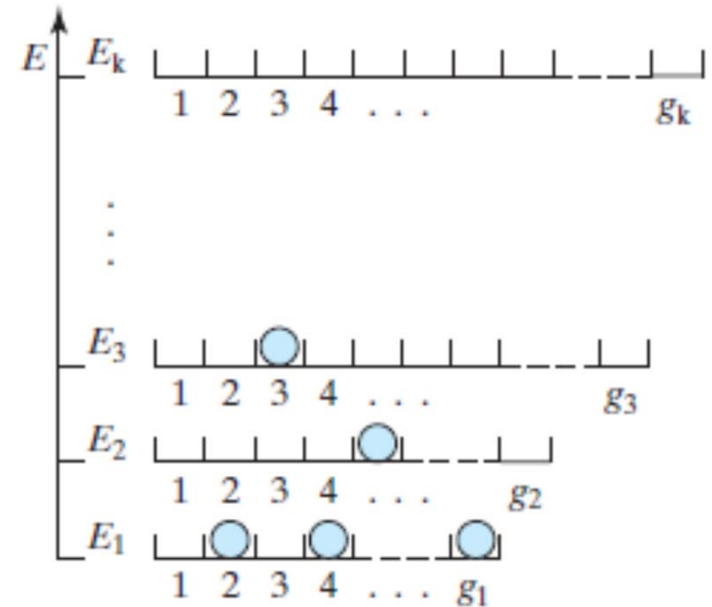
- Band comprises discrete energy levels
  - There are  $g_1$  states at  $E_1$ ,  $g_2$  states at  $E_2$ ...
- There are  $N$  electrons, which constantly shift among all the states but the average electron energy is fixed at  $3kT/2$ .

- There are many ways to distribute  $N$  among  $n_1, n_2, n_3$ ...and satisfy the  $3kT/2$  condition.

- The equilibrium distribution is the distribution that maximizes the number of combinations of placing  $n_1$  in  $g_1$  slots,  $n_2$  in  $g_2$  slots.... :

$$n_i/g_i = \frac{1}{1 + e^{(E_i - E_f)/kT}}$$

$E_F$  is a constant determined by the condition  $\sum n_i = N$





# Fermi-Dirac distribution $f(E)$

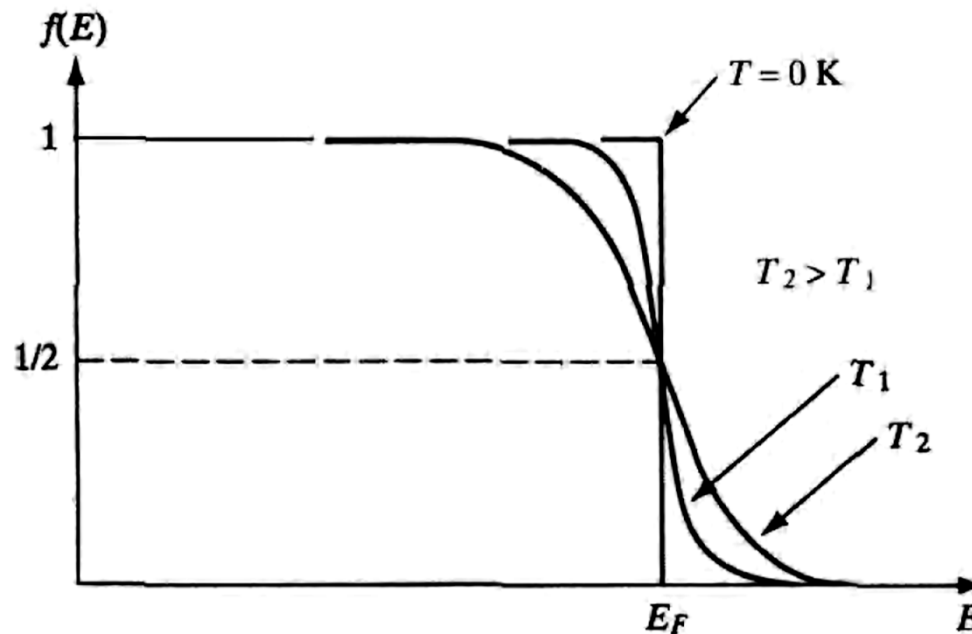
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$$f(E) = \frac{1}{1 + e^{(E-E_f)/kT}}$$

$E_f$  is called the *Fermi energy* or the *Fermi level*

Boltzmann approximation:

$$f(E) \approx e^{-(E-E_f)/kT} \quad \begin{array}{l} E - E_f \gg kT \\ E - E_f > 3kT \end{array}$$

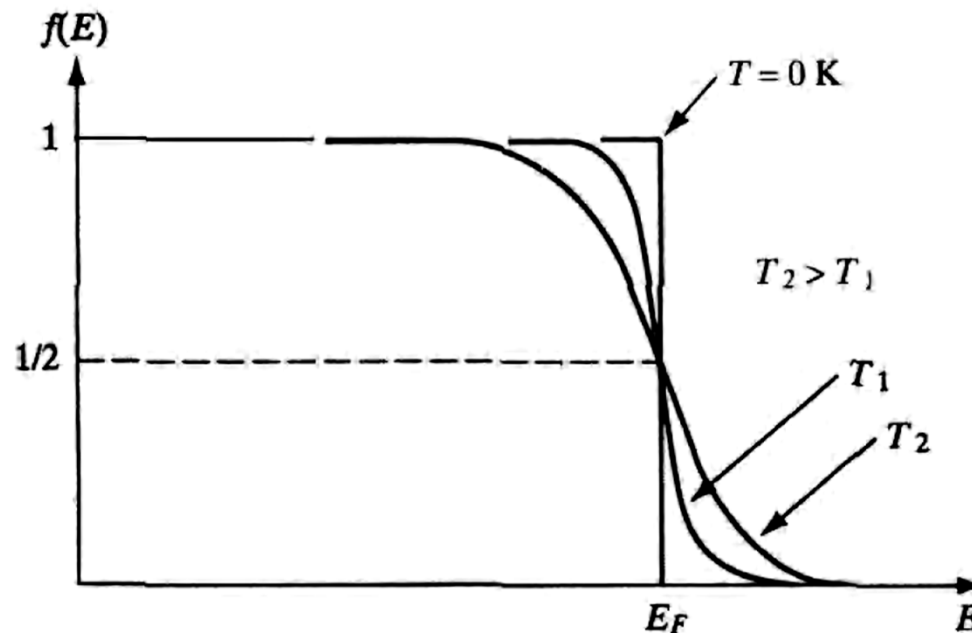


# Fermi-Dirac distribution $f(E)$

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$$f(E) = \frac{1}{1 + e^{(E - E_f)/kT}}$$

$E_f$  is called the *Fermi energy* or the **Fermi level**

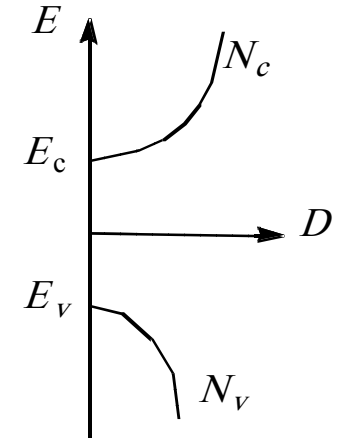
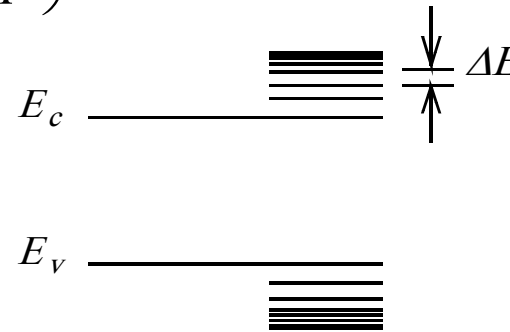


- **Fermi level** is the energy at which probability of occupancy equals  $1/2$
- **Fermi level** is the topmost filled energy level at 0 K
- As  $T$  increases, the tail of pdf extends as it becomes more probable that electrons fill states with higher energy due to thermal agitation
- F-D distribution is symmetric about  $E_f$  at all  $T$ , i.e.  $f(E_f + E_1) = 1 - f(E_f - E_1)$

# Density of states $N_c(E)$ , $N_v(E)$

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$$N_c(E) \equiv \frac{\text{number of states in } \Delta E}{\Delta E \cdot \text{volume}} \left( \frac{1}{\text{eV} \cdot \text{cm}^3} \right)$$



$$N_c(E)dE = \frac{8\pi\sqrt{2}}{h^3} (m_n^*)^{3/2} \sqrt{E - E_c} dE$$

$$N_v(E)dE = \frac{8\pi\sqrt{2}}{h^3} (m_p^*)^{3/2} \sqrt{E_v - E} dE$$

- The density of available states increases as their energies increase
- Analogy with for example Hydrogen atom, the larger the energy (higher  $n$ ), the more the available states at these higher energies (more subshells)

# Derivation of carrier concentration $n_0$ and $p_0$

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$$n_0 = \int_{E_c}^{\text{top of conduction band}} f(E) N_c(E) dE$$

Boltzmann approximation:

$$f(E) \approx e^{-(E-E_f)/kT}$$

$$n_0 \approx \frac{8\pi\sqrt{2}}{h^3} (m_n^*)^{3/2} \int_{E_c}^{\infty} \sqrt{E - E_c} e^{-(E-E_f)/kT} dE$$

$$= \frac{8\pi\sqrt{2}}{h^3} (m_n^*)^{3/2} e^{-(E_c-E_f)/kT} \int_0^{\infty} \sqrt{E - E_c} e^{-(E-E_c)/kT} d(E - E_c)$$

$$= N_c e^{-(E_c-E_f)/kT}$$

$$\frac{\sqrt{\pi}}{2} (kT)^{3/2}$$

# Derivation of carrier concentration $n_0$ and $p_0$

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$$n_0 = N_c e^{-(E_c - E_f)/kT}$$

$$N_c \equiv 2 \left[ \frac{2\pi m_n^* kT}{h^2} \right]^{3/2}$$

$$p_0 = N_v e^{-(E_f - E_v)/kT}$$

$$N_v \equiv 2 \left[ \frac{2\pi m_p^* kT}{h^2} \right]^{3/2}$$

$N_c$  is called the ***effective density of states (of the conduction band)***.

$N_v$  is called the ***effective density of states of the valence band***.

- Looking at formulas, as  $n_0$  increases (due to n-doping for example)  $E_f$  moves closer to  $E_c$  and similarly  $p_0$  increases as  $E_f$  moves closer to  $E_v$
- For Si at  $T=300$  K,  $m_n^* = 1.1m_0 \rightarrow N_c = 2.8 \times 10^{19} \text{ cm}^{-3}$
- For Si at  $T=300$  K,  $m_p^* = 0.57m_0 \rightarrow N_v = 1.04 \times 10^{19} \text{ cm}^{-3}$

## Product of $n_0$ and $p_0$ (Either intrinsic or extrinsic)

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$$\left. \begin{aligned} n_0 &= N_c e^{-(E_c - E_f)/kT} \\ p_0 &= N_v e^{-(E_f - E_v)/kT} \end{aligned} \right\} \begin{aligned} n_0 p_0 &= N_c N_v e^{-(E_c - E_v)/kT} \\ &= N_c N_v e^{-E_g/kT} \end{aligned}$$

- Product of  $n_0$  and  $p_0$  formula holds even if the SC is doped since it only depends on  $N_c$ ,  $N_v$  and  $E_g$  where none of them changes with doping !! (**Very important**)

# Intrinsic carrier concentration $n_i$

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$$n_0 = N_c e^{-(E_c - E_f)/kT}$$

$$p_0 = N_v e^{-(E_f - E_v)/kT}$$

$$n_0 p_0 = N_c N_v e^{-(E_c - E_v)/kT}$$

$$= N_c N_v e^{-E_g/kT}$$



$$n_0 = p_0 = n_i \quad (\text{Intrinsic})$$

$$n_i = \sqrt{N_c N_v} e^{-E_g/2kT}$$

■ For Si at  $T=300$  K,  $N_c = 2.8 \times 10^{19} \text{ cm}^{-3}$ ,  $N_v = 1.04 \times 10^{19} \text{ cm}^{-3}$ ,  $E_g = 1.1 \text{ eV}$   
substitute above to get

$$n_i = 10^{10} \text{ cm}^{-3}$$

# Intrinsic Fermi level $E_i$

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$$n_0 = p_0$$

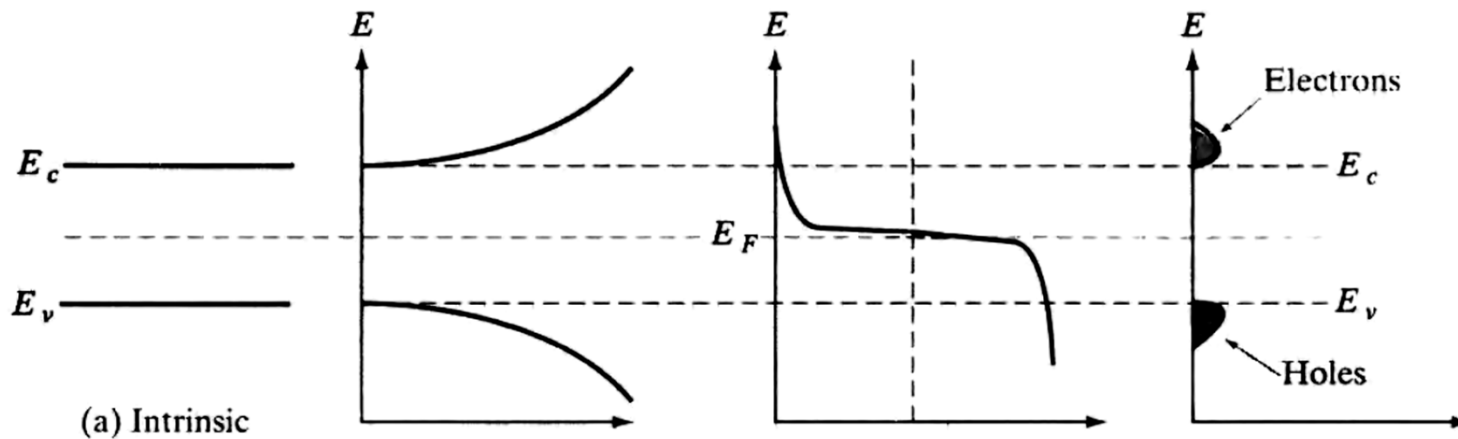
$$N_c e^{-(E_c - E_i)/kT} = N_v e^{-(E_i - E_v)/kT}$$

$$E_i = \frac{E_c + E_v}{2} + \frac{kT}{2} \ln\left(\frac{N_v}{N_c}\right)$$

$$E_i \approx \frac{E_c + E_v}{2}$$



$E_i$  lies (almost) in the middle between  $E_c$  and  $E_v$





What happens to  $E_f$  if we dope the SC (change  $n_0$  from  $n_i$ )?

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$$\begin{aligned} n_0 &= N_c e^{-(E_c - E_f)/kT} \\ n_i &= N_c e^{-(E_c - E_i)/kT} \\ N_c &= n_i e^{(E_c - E_i)/kT} \\ n_0 &= n_i e^{(E_c - E_i)/kT} \cdot e^{-(E_c - E_f)/kT} \end{aligned}$$

$$n_0 = n_i e^{(E_f - E_i)/kT}$$

$$\therefore E_f = E_i + kT \ln \left( \frac{n_0}{n_i} \right)$$

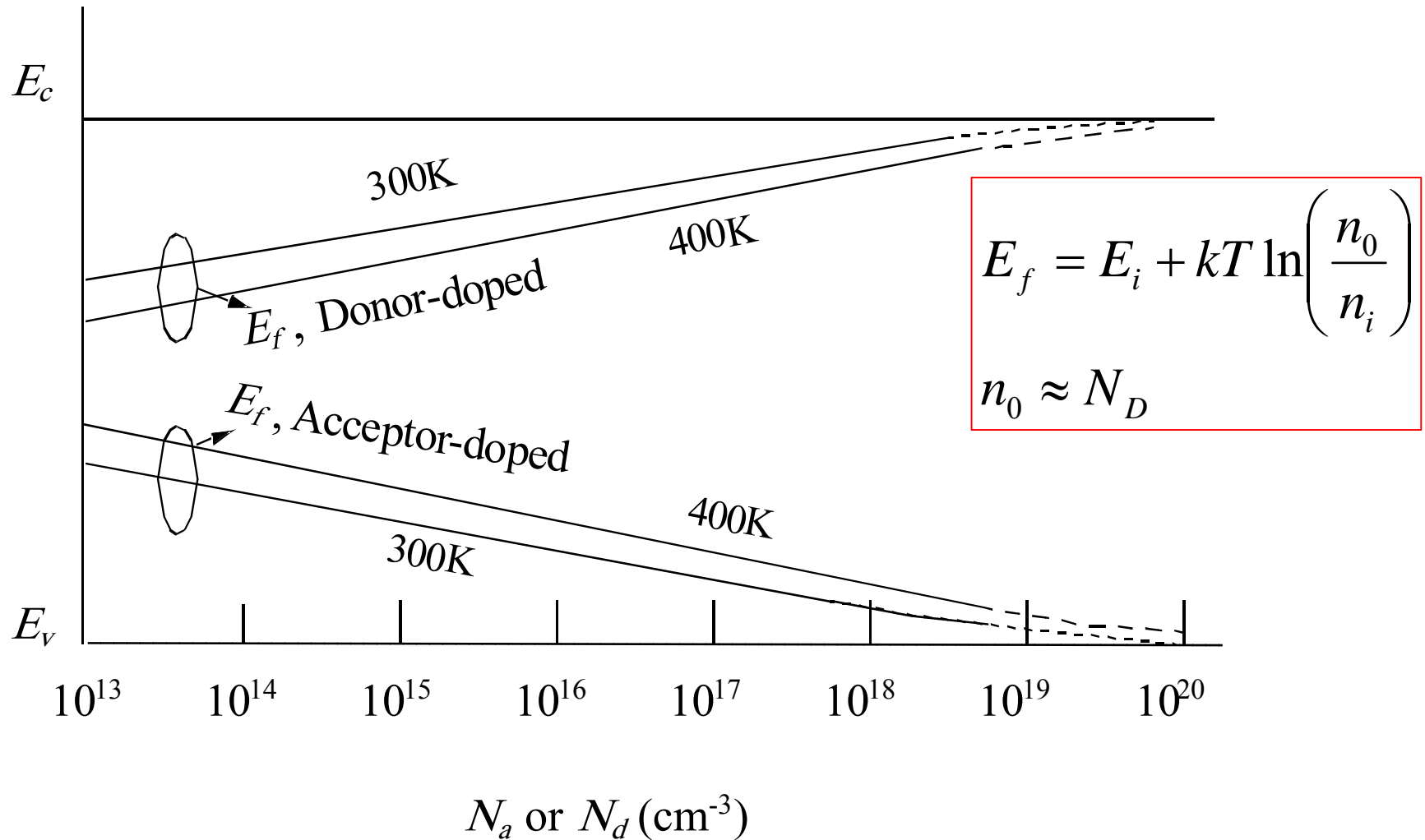
$$\begin{aligned} p_0 &= N_v e^{-(E_f - E_v)/kT} \\ n_i &= N_v e^{-(E_i - E_v)/kT} \\ N_v &= n_i e^{(E_i - E_v)/kT} \\ p_0 &= n_i e^{(E_i - E_v)/kT} \cdot e^{-(E_f - E_v)/kT} \end{aligned}$$

$$p_0 = n_i e^{(E_i - E_f)/kT}$$

$$\therefore E_f = E_i - kT \ln \left( \frac{p_0}{n_i} \right)$$

What happens to  $E_f$  if we dope the SC (change  $n_0$  from  $n_i$ )?

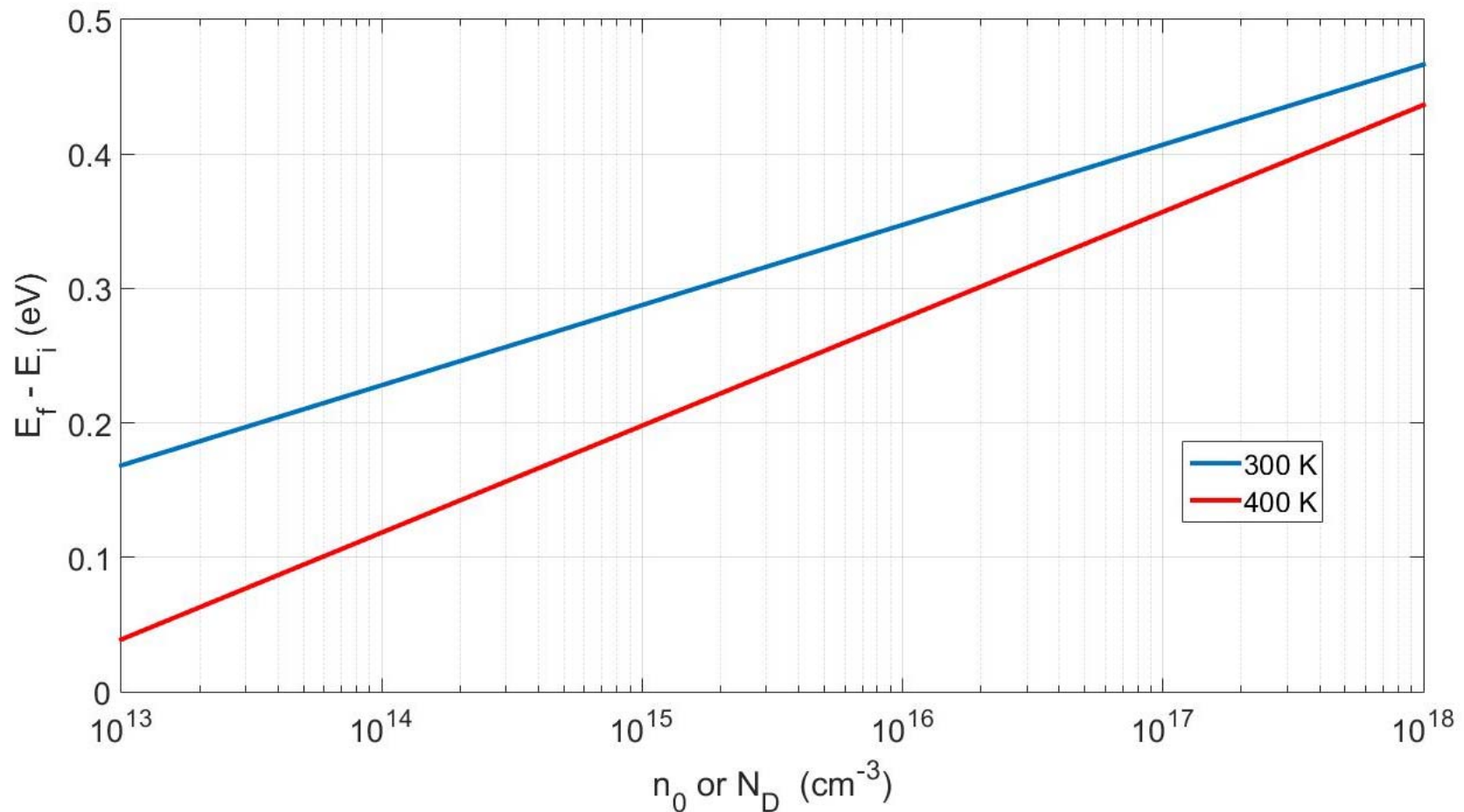
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# Take home exercise

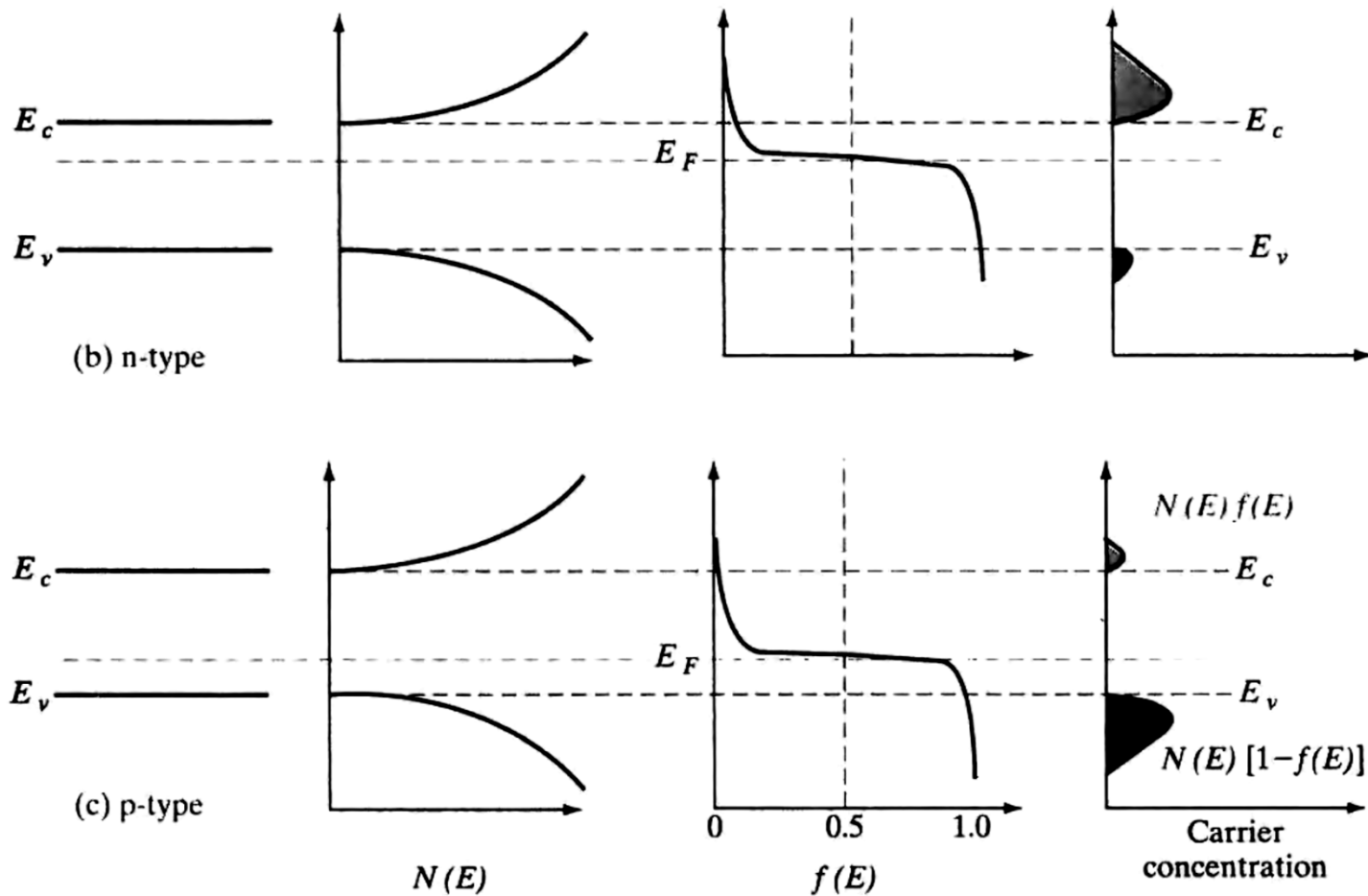
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- Plot on MATLAB  $E_f - E_i$  for Si at both  $T = 300\text{K}$  and  $400\text{K}$  (Hint: you have to find  $n_i$  at  $300\text{K}$  and  $400\text{K}$  using  $m_n^* = 1.1m_0$ ,  $m_p^* = 0.57m_0$ ,  $E_g = 1.1\text{ eV}$ )



# What happens to $E_f$ if we dope the SC?

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# Numerical example

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■ A Si sample is doped with  $10^{17}$  As atoms/cm<sup>3</sup>. What is the equilibrium hole concentration at 300 K? Where is  $E_f$  relative to  $E_i$ ? Where is  $E_f$  relative to  $E_c$ ? (use  $n_i = 1.5 \times 10^{10}$  cm<sup>-3</sup> at this temperature)

$$n_0 \approx N_D = 10^{17} \text{ cm}^{-3}$$

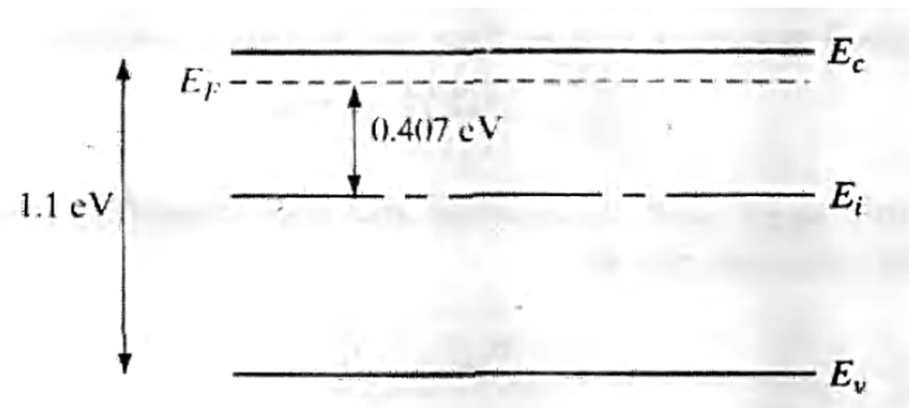
$$p_0 = \frac{n_i^2}{n_0} = 2.25 \times 10^3 \text{ cm}^{-3}$$

$$\therefore n_0 = n_i e^{(E_f - E_i)/kT}$$

$$\therefore E_f = E_i + kT \ln\left(\frac{n_0}{n_i}\right)$$

$$E_f - E_i = 0.0259 \ln\left(\frac{10^{17}}{1.5 \times 10^{10}}\right) = 0.407 \text{ eV}$$

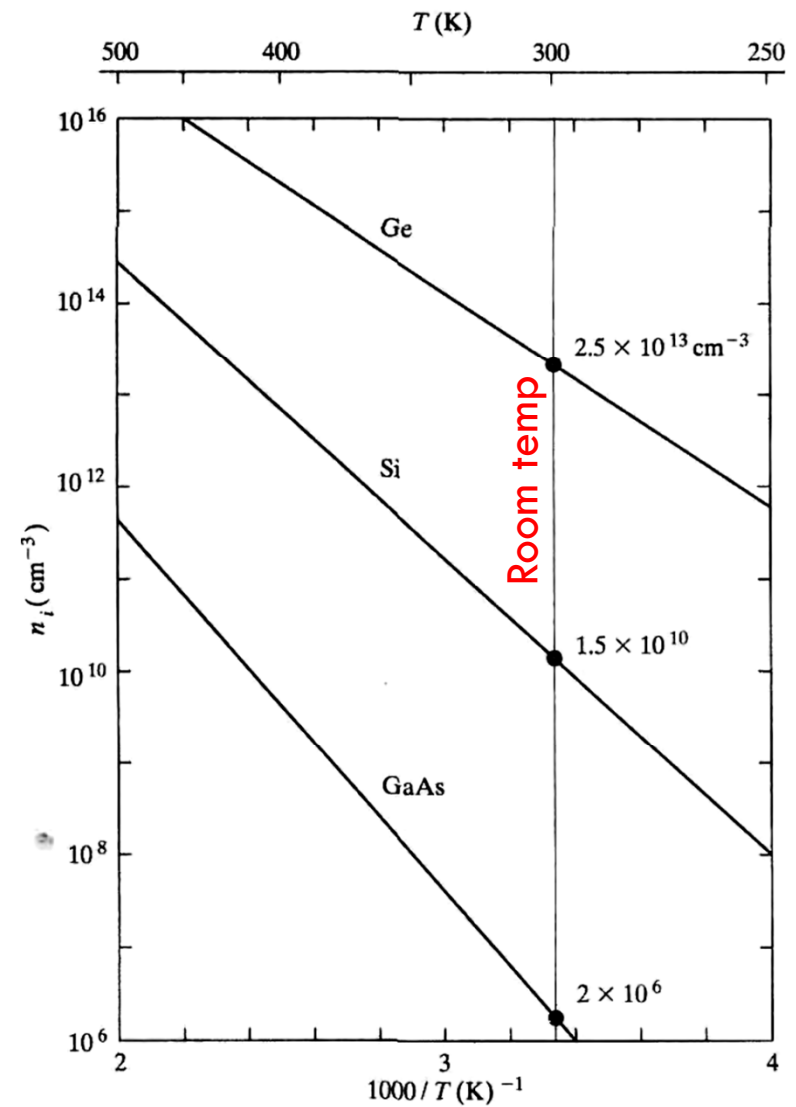
$$\therefore E_c - E_f = 0.5E_g - (E_f - E_i) = 0.55 - 0.407 = 0.143 \text{ eV}$$



# Effect of temperature on $n_i$

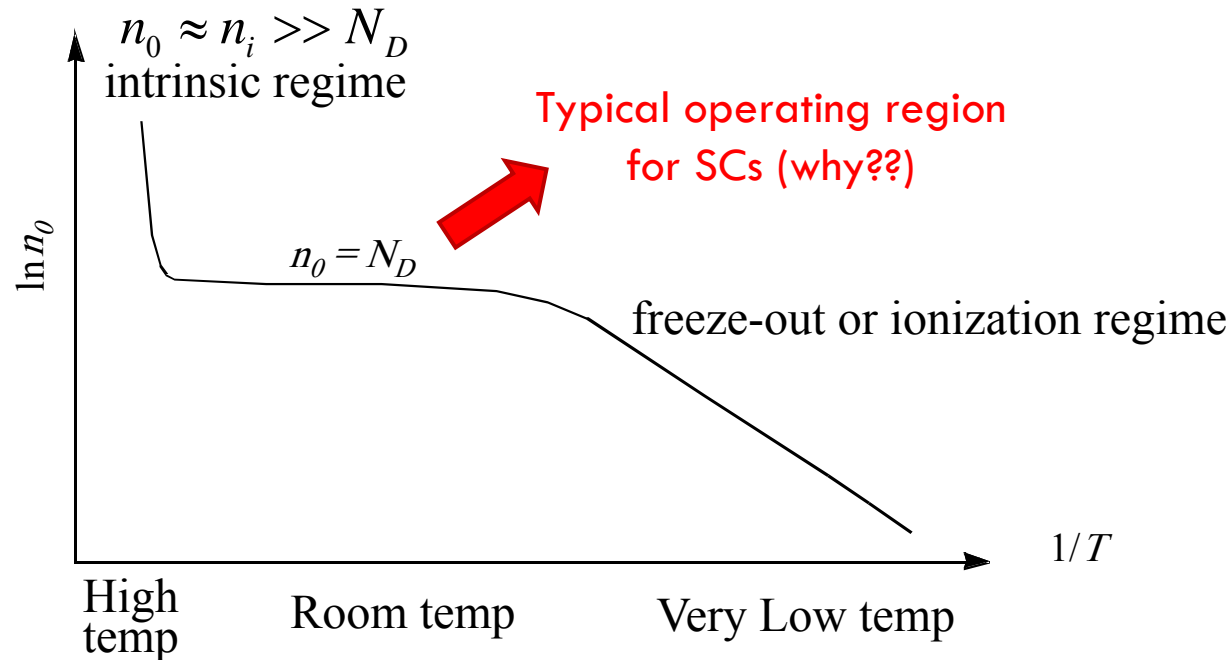
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$$n_i(T) = 2 \left( \frac{2\pi kT}{h^2} \right)^{3/2} (m_n^* m_p^*)^{3/4} e^{-E_g/2kT}$$



# Effect of temperature on $n_0$ for a n-type SC

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high T:  $n = p = n_i = \sqrt{N_c N_v} e^{-E_g/2kT}$

Thermally gen. Intrinsic EHPs dominate donor electrons

low T:  $n = \left[ \frac{N_c N_D}{2} \right]^{1/2} e^{-(E_c - E_d)/2kT}$

Donor electrons are the only free electrons in CB (no intrinsic EHP)